

		<div><div><div>बि एच ई एल</div><div>BHEL</div></div><div>A4 - 10</div></div>		<div>PS- 439 - 109</div> <div>REV. No. 02</div> <div>PAGE 02 OF 02</div>	
		<div>3.0 CHARACTERISTICS</div> <div><div><div>3.1</div><div>TYPE</div><div>P(Boron doped)</div><div>ASTM-F42</div></div><div><div>3.2</div><div>ORIENTATION</div><div><100> ± 3.0 Deg.</div><div>ASTM-F26</div></div><div><div>3.3</div><div>RESISTIVITY</div><div>0.5 – 3.0 ohm.cm</div><div>Four point probe</div></div><div><div>3.4</div><div>OXYGEN CONCENTRATION</div><div><=1 x 10¹⁸ Atoms/CM³</div><div>ASTM-F121</div></div><div><div>3.5</div><div>CARBON CONCENTRATION</div><div><=1 x 10¹⁷ Atoms/CM³</div><div>ASTM-F123</div></div><div><div>3.6</div><div>Life Time</div><div>>= 10 micro seconds</div><div>ASTM F28-91</div></div></div>			
		<div>4.0 PACKING</div> <div><div><div>1. Wafers shall be kept sealed in polythene / polypropylene sachets.</div><div>2. Each sachets shall have not more than 100 wafers with a label giving manufacturer name, Ingot no., quantity and wafer characteristics.</div><div>3. Sachets shall be packed in thermocole boxes with soft spacers on both ends or in polyethylene foam packing to absorb transit handling shocks. Final packing shall be in carton/wooden cases for easy handling. Wooden cases shall be suitable for air freight.</div><div>4. Each lot must be accompanied with a test certificate containing actual values in the format given below.</div></div><div><div>.....</div><div><div>Characteristics</div><div>Value Specified</div><div>Actuals Observed</div><div>Test Procedure / standards followed.</div></div><div>.....</div></div></div>			
		<div>5.0 BHEL ACCEPTANCE / INSPECTION PLAN</div> <div><div>Inspection of wafers shall be carried out either in BHEL or at the supplier's works as per single sampling plan IS 2500 (Part I) , Inspection level II and Acceptance Quality Level (AQL) of 0.65 % for visual inspections and IS 2500 (Part II), Inspection level IV and AQL of 0.65 % for dimensional and resistivity measurements.</div></div>			



A4-10

**PURCHASE SPECIFICATION
GROUP : PHOTOVOLTAICS****PS- 439 - 016**

REV. 04

PAGE 01 OF 02

TECHNICAL SPECIFICATION

1. MATERIAL : 125 mm Square Multi crystalline silicon wafer
2. APPLICATION : It is used as starting material for Solar Photovoltaic cells production.

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SL. NO.	CHARACTERISTICS	VALUE	UNIT	TESTING METHODS / REF. STANDARDS.
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1.0	APPEARANCE	As cut cleaned	Unaided Visual inspection.
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1.2 SURFACE CONDITION

Wafers after slicing shall be subjected to detergent solution cleaning process and ultrasonic degreasing process for removal of greases, stains etc. It shall be not be subjected to any kind of chemical etching.

1.2	SAW MARKS DEPTH	<=30 microns	Visual inspection and surface profiling.
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4.0 DIMENSIONS

2.1	Size (Side to Side)	125±1 mm	Vernier/Go-No Go gauges
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2.2	Shape	Square
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2.3	Thickness	220±20 microns	ASTM-F533
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2.4	TTV (Total Thickness Variation)	<=50 microns	ASTM-F533
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2.5	BOW	<=70 microns	ASTM-F534
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Rev. 04
Thickness revised.

APPROVED BY :

SS

PREPARED

SR

ISSUED


Engg.

DATE

30-04-2008

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			PURCHASE SPECIFICATION GROUP : PHOTOVOLTAICS		PS- 439 - 016
					REV. No. 04
					PAGE 02 OF 02
COPY RIGHT AND CONFIDENTIAL The information on this document is the property of Bharat Heavy Electrical Limited. It must not be used directly or indirectly in anyway detrimental to the interest of the company.		A4 - 10	5.0 CHARACTERISTICS		
			3.1	TYPE	P(Boron doped) ASTM-F42
			3.2	RESISTIVITY	0.5 – 3.0 ohm.cm Four point probe
			3.3	OXYGEN CONCENTRATION	$\leq 1 * 10^{18}$ Atoms/CM ³ ASTM-F121
			3.4	CARBON CONCENTRATION	$\leq 2 * 10^{18}$ Atoms/CM ³ ASTM-F123
			3.5	Life time	> 2 micro seconds ASTM F28-91
			4.0 PACKING		
			5. Wafers shall be kept sealed in polythene / polypropylene sachets. 6. Each sachets shall have not more than 100 wafers with a label giving manufacturer name, Casting no., quantity and wafer characteristics. 7. Sachets shall be packed in thermocole boxes with soft spacers on both ends or in polyethylene foam packing to absorb transit handling shocks. Final packing shall be in carton/wooden cases for easy handling. 8. Each lot must be accompanied with a test certificate containing actual values in the format given below.		
				
			Characteristics	Value Specified	Actuals Observed Test Procedure / standards followed.
				
			5.0 BHEL ACCEPTANCE / INSPECTION PLAN		
			Inspection of wafers shall be carried out either in BHEL or at the supplier's works as per single sampling plan IS 2500 (Part I) , Inspection level II and Acceptance Quality Level (AQL) of 0.65 % for visual inspections and IS 2500 (Part II), Inspection level IV and AQL of 0.65 % for dimensional and resistivity measurements.		



A4-10

**PURCHASE SPECIFICATION
GROUP : PHOTOVOLTAICS****PS- 439 - 093**

REV. 01

PAGE 01 OF 02

TECHNICAL SPECIFICATION

1. MATERIAL : 156 mm Square Multi crystalline silicon wafer
2. APPLICATION : It is used as starting material for Solar Photovoltaic cells production.

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SL. NO.	CHARACTERISTICS	VALUE	UNIT	TESTING METHODS / REF. STANDARDS.
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1.0	APPEARANCE	As cut cleaned	Unaided Visual inspection.
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1.3 SURFACE CONDITION

Wafers after slicing shall be subjected to detergent solution cleaning process and ultrasonic degreasing process for removal of greases, stains etc. It shall be not be subjected to any kind of chemical etching.

1.2	SAW MARKS DEPTH	≤ 20 microns	Visual inspection and surface profiling.
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6.0 DIMENSIONS

2.1	Size (Side to Side)	156 ± 1 mm	Vernier/Go-No Go gauges
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2.2	Shape	Square
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2.3	Thickness	220 ± 20 microns	ASTM-F533
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2.4	TTV (Total Thickness Variation)	≤ 50 microns	ASTM-F533
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2.5	BOW	≤ 70 microns	ASTM-F534
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(01) Thickness revised.

APPROVED BY :

SS

PREPARED

SR

ISSUED

Engg.

DATE

30-04-2008

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